# **Electronic Supplementary Information**

## Defect engineered TiO<sub>2</sub> nanotube photonic crystals for

### fabrication of near-infrared photoelectrochemical sensor

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- Fig. S1. Top-view SEM image of one-step anodized TiO<sub>2</sub> NTs.
- Fig. S2. Top-view SEM image of nanoconcaves.
- Fig. S3. Cross-sectional SEM image of TiO<sub>2</sub> NTPCs.
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- Fig. S10. (a) Electrochemical impedance spectra of TiO<sub>2</sub> NTPCs, DE-TiO<sub>2</sub> NTPCs, and DA/DE-TiO<sub>2</sub> NTPCs, (b) enlarged EIS of DE-TiO<sub>2</sub> NTPCs, and DA/DE-TiO<sub>2</sub> NTPCs, the insets are corresponding equivalent circuits.
- *Fig. S11. PEC performance of TiO*<sub>2</sub> *NTs and DE-TiO*<sub>2</sub> *NTs under illumination of NIR light.*
- *Fig. S12. Reproducibility, repeatability, and stability measurements of DE-TiO*<sub>2</sub> *NTPCs.*

#### **Reference** list



Fig. S1 Top-view SEM image of one-step anodized TiO<sub>2</sub> NTs.



Fig. S2 Top-view SEM image of nanoconcaves.



Fig. S3 Cross-sectional SEM image of TiO<sub>2</sub> NTPCs.



**Fig. S4** HRTEM image of TiO<sub>2</sub> NTPCs.



Fig. S5 XPS survey of TiO<sub>2</sub> NTPCs, DE-TiO<sub>2</sub> NTPCs, and DA/DE-TiO<sub>2</sub> NTPCs.



Fig. S6 DRS of TiO<sub>2</sub> NTs.



Fig. S7 Digital photos of (a) TiO<sub>2</sub> NTPCs and (b) DE-TiO<sub>2</sub> NTPCs.



**Fig. S8** Top-view SEM image of DE-TiO<sub>2</sub> NTPCs annealed at (a) 500 °C and 550 °C, (c) photocurrent density of DE-TiO<sub>2</sub> NTPs annealed at different temperature, and (d) photocurrent density of DE-TiO<sub>2</sub> NTPCs with different vacummized time.

The DE-TiO2 NTPCs annealed at 350 °C and 400 °C showed similar morphologies

(no presented here) with DE-TiO<sub>2</sub> NTPCs annealed at 450 °C, further increased the temperature beyond 500 °C, the top ordered nanoring structure will be destroyed and loss the light harvesting ability (Fig. S8a,b), which will consequently decrease the NIR PEC performance (Fig. S8c). The vacummized time before annealing was also optimized, as showed in Fig. S8d, the DE-TiO<sub>2</sub> NTPCs presented steady PEC performance after 60 seconds vacummization. Thus the defect engineering condition is optimized to 60 seconds vacummization and 450 °C annealing.



Fig. S9 Mott-Schottky plots of  $TiO_2$  NTPCs and DE- $TiO_2$  NTPCs at a fixed frequency of 5 kHz, the inset is magnified plot of DE- $TiO_2$  NTPCs.

Mott-Schottky (MS) electrochemical impedance measurements were conducted in this study to display the capacitance change after defect engineering process. The MS plots of TiO<sub>2</sub> NTPCs and DE-TiO<sub>2</sub> NTPCs were presented in Fig. S9, and the semiconductor type, flat band potential ( $U_{\rm FB}$ ) and carrier density ( $N_{\rm D}$ ) were determined following the equation below:<sup>1</sup>

$$\frac{1}{C^2} = \frac{2}{N_D e \varepsilon_0 \varepsilon} [(U_S - U_{FB}) - \frac{k_B T}{e}]$$
(1)

where C is the space charge capacitance in the semiconductor;  $N_{\rm D}$  is the electron carrier density; e is the elementary charge value;  $\varepsilon^0$  is the permittivity of the vacuum;  $\varepsilon$  is the relative permittivity of the semiconductor;  $U_{\rm s}$  is the applied potential; *T* is temperature; and k<sub>B</sub> is the Boltzmann constant. The positive slopes of the linear part of the curves in MS plots indicated that the defect engineering did not change the n-type semiconductor property of TiO<sub>2</sub>. The  $U_{\rm FB}$  were estimated to be -0.33 V and -0.50 V for TiO<sub>2</sub> NTPCs and DE-TiO<sub>2</sub> NTPCs respectively. The negative shift of  $U_{\rm FB}$  suggested steeper band bending, which would facilitate the charge separation at the semiconductor/electrolyte interface. The carrier density  $N_{\rm D}$  was determined from Fig. S9 using the following equation:<sup>1</sup>

$$N_D = -\left(\frac{2}{e\varepsilon\varepsilon_0}\right) \left(\frac{d(1/C^2)}{d(U_s)}\right)^{-1}$$
(2)

with  $e = -1.6 \times 10^{-19}$ ,  $\varepsilon^0 = 8.86 \times 10^{-12}$ , and  $\varepsilon = 48$  for anatase TiO<sub>2</sub><sup>2</sup>. The pristine TiO<sub>2</sub> NTPCs showed a  $N_D$  of  $1.5 \times 10^{18}$  cm<sup>-3</sup>, while the DE-TiO<sub>2</sub> NTPCs showed a much higher  $N_D$  of  $2.4 \times 10^{19}$  cm<sup>-3</sup>.



Fig. S10. (a) Electrochemical impedance spectra of TiO<sub>2</sub> NTPCs, DE-TiO<sub>2</sub> NTPCs, and DA/DE-TiO<sub>2</sub> NTPCs, (b) enlarged EIS of DE-TiO<sub>2</sub> NTPCs, and DA/DE-TiO<sub>2</sub> NTPCs, the insets are corresponding equivalent circuits.

Electrochemical impedance spectra (EIS) measurements were carried out for understanding the electronic modification after defect engineering process. As presented in Fig. S10a, the DE-TiO<sub>2</sub> NTPCs showed a much lower charge transfer resistance than TiO<sub>2</sub> NTPCs, implying the enriched defects (oxygen vacancies) significantly increased its electronic conductivity. The significantly enhanced electronic conductivity can be well explained from the increased carrier density (Fig. S9). After adsorption of DA on the surface of DE-TiO<sub>2</sub> NTPCs, a lower electron transfer resistance was also presented in Fig. S10b, which implied efficient charge transfer between DA and DE-TiO<sub>2</sub> NTPCs.



Fig. S11 PEC performance of  $TiO_2$  NTs and DE- $TiO_2$  NTs under illumination of NIR light.



Fig. S12 Reproducibility, repeatability, and stability measurements of  $DE-TiO_2$  NTPCs.

The detection reproducibility of batch sensors was investigated by measuring the response photocurrent of 6 photoelectrode, as shown in Fig. S12a, a relative standard deviation of 1.59% was achieved. The repeatability was measured with one electrode for 8 times and a relative standard deviation (RSD) of 2.27% was obtained (Fig. S12b).

Furthermore, the long-term stability of the PEC sensors was also tested by studying the current response intermittently in a period of 15 days (Fig. S12c), and no obvious photocurrent differences were found.

#### **Reference list**

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